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| Session Title: | [MA2] Advanced Atomic Scale Thin Films II |
| Session Date: | November 20 (Mon.), 2023 |
| Session Time: | 14:55-16:40 |
| Session Room: | Room A (Capri Room, 2F) |
| Session Chair: | Prof. Woo Hee Kim (Hanyang Univ., Korea) |

[MA2-1] [Plenary] 14:55-15:40

Elevating Atomic Layer Deposition to the Angstrom Era

W.M.M. (Erwin) Kessels (Eindhoven Univ. of Tech., The Netherlands)

[MA2-2] [Invited] 15:40-16:00

Hybrid Multilayer EUV Photoresist for 1.5 Technology Node

Myung Mo Sung (Hanyang Univ., Korea)

[MA2-3] [Invited] 16:00-16:20

Atomic Layer Deposition for Nanoscale Oxide Semiconductor Field Effect Transistors: Four Values and Outlook

Dong-Gyu Kim, Yoon Seo Kim, Hye Mi Kim, and Jin-Seong Park (Hanyang Univ., Korea)

[MA2-4] 16:20-16:40

High Throughput SiO₂ Thin Films Using Novel Si Precursors

Jinsik Kim, Byung Kwan Kim, Da Som Yu, Seunggyun Hong, In Jae Lee, Hyun Kyu Ryu, and Wonyong Koh (UP Chemical, Korea)